China factory High Purtiy Hcds 99.9% Si2cl6 Hexachlorodisilane

Our Product Introduction

Basic Information

- Place of Origin: China
- Brand Name: CMC
- Certification: COA
- Model Number: Si2cl6
- Minimum Order Quantity: 1kg
- Price: US $40/kg
- Packaging Details: Cylinder/Tank
- Delivery Time: 15 days
- Payment Terms: L/C, T/T
- Supply Ability: 50000kg/month

Product Specification

- Product Name: Hexachlorodisilane
- Model No.: Si2cl6
- Transport: By Sea
- Purity: 99.9%
- Transport Package: Cylinder
- Specification: 40L, 200L
- Trademark: CMC
- Origin: China
- HS Code: 2812190091
- Supply Ability: 100t/Year
- CAS No.: 7783-82-6
- Formula: Si2cl6
- EINECS: 7783-82-6
- Constituent: Industrial Pure Air
- Grade Standard: Industrial Grade

More Images

Product Description

Product Description

Hexachlorodisilane (Si_2Cl_6) is an inorganic compound consisting of two silicon (Si) atoms bonded together with six chlorine (Cl) atoms. It is a colorless gas that is primarily used as a precursor in the production of silicon-based materials. Here are some key points about hexachlorodisilane gas:

Structure and Properties: Hexachlorodisilane has a tetrahedral molecular structure, with each silicon atom bonded to three chlorine atoms and the other silicon atom. It is a volatile and reactive compound, and its boiling point is around 140 °C.

Synthesis and Production: Hexachlorodisilane is typically synthesized by the reaction of silicon tetrachloride ($SiCl_4$) with elemental silicon (Si) or silicon powder at high temperatures. It can also be produced through the reaction of silicon with chlorine gas (Cl_2).

Applications:

Semiconductor Industry: Hexachlorodisilane is a crucial precursor in the production of various silicon-based thin films for the semiconductor industry. It is used in chemical vapor deposition (CVD) and atomic layer deposition (ALD) processes to deposit silicon-containing layers with high purity and uniformity.

Silicon Nitride Production: Hexachlorodisilane can be used as a precursor for the synthesis of silicon nitride (Si_3N_4) ceramics. It reacts with ammonia (NH_3) to form silicon nitride, which is used in the manufacturing of ceramics, cutting tools, and protective coatings.

Surface Modification: Hexachlorodisilane is employed as a surface treatment agent to modify the surface properties of materials. It can enhance hydrophobic or hydrophilic characteristics, improve adhesion, or provide chemical resistance to surfaces.

Safety Considerations: Hexachlorodisilane is a highly reactive and volatile compound. It is corrosive to metals and can cause severe burns upon contact with the skin or eyes. It is also toxic if inhaled or ingested. Proper handling, storage, and personal protective equipment should be used when working with hexachlorodisilane or any other hazardous chemicals.

Hexachlorodisilane gas is an important precursor in the semiconductor industry and the production of silicon-based materials. Its reactivity and ability to deposit high-quality silicon films make it valuable for various technological applications. However, it should be handled with caution due to its hazardous properties.

Basic Info.

Model NO.	Si_2Cl_6	Grade Standard	Electron Grade
Transport Package	Cylinder, Canister	Specification	40L, 200L
Trademark	CMC	Origin	Suzhou, China
HS Code	2812190091	Production Capacity	100t/Year

Specifications:

IUPAC name	Hexachlorodisilane
Other names	Disilicon hexachloride
Identifiers	
CAS No.:	13465-77-5
EC No.:	236-704-1
Properties	
Molecular Formula:	Si_2Cl_6
Molar mass:	268.88 g/mol
Appearance:	Colorless liquid
Melting point:	≤20 °C
Boiling point:	144 °C (291 °F; 417 K)
Flash point:	>93°C
Vopor density(Air=1):	>1
Relative density(Water=1):	1.562

Sample Test:

Test Items	Units	Specifications	Test Result
Assay by GC	wt%	≥99.9	99.905
Li	ng/g	≤0.5	<0.05
Na	ng/g	≤0.5	<0.05
Mg	ng/g	≤0.5	<0.05
Al	ng/g	≤1.0	0.35
K	ng/g	≤0.5	0.08
Ca	ng/g	≤0.5	0.16
Ti	ng/g	≤1.0	0.18
Cr	ng/g	≤0.5	<0.05
Mn	ng/g	≤0.5	<0.05
Fe	ng/g	≤1.0	0.48
Co	ng/g	≤0.5	<0.05

Ni	ng/g ≤0.5	0.06
Cu	ng/g ≤0.5	<0.05
Zn	ng/g ≤0.5	<0.05

Detailed Photos


六氯乙硅烷
编号 V200S013
怕 湿
向 上


化学品名称 六氯乙硅烷
HEXACHLORODISILANE
CAS No.: 13465-77-6
含量：100%
危 险
造成严重皮肤灼伤和眼损伤。
【预防措施】
• 不要吸入粉尘/烟/气体/烟雾/蒸气/喷雾。
• 作业后彻底清洗。
• 戴防护手套/穿防护服/戴防护眼罩/戴防护面具。
【事故响应】
• 立即呼叫中毒急救中心/医生。
• 沾染的衣服清洗后方可重新使用。
• 如误吸入：将受人转移到空气新鲜处，保持
• 如误吞咽：漱口，不要诱导呕吐。
• 如皮肤（或头发）沾染：立即去除/脱掉所有沾染的衣服。用水清洗皮肤或淋浴。
• 如进入眼睛：用水小心冲洗几分钟。如戴隐形眼镜且可方便地取出，取出隐形眼镜。继续冲洗
【安全储存】
• 存放处须加锁
【废弃处置】
• 按照地方/区域/国家/国际规章处置内装物/容器。
请参阅化学品安全技术说明书
供应商：洛阳中硅高科技有限公司一分公司
电话：0379-68808102
地 址：洛阳市洛龙科技园区杜月大道四路 1 号
邮 编：471000
化学事故国内应急咨询电话：0379-68808119

Shanghai Kemike Chemical Co.,Ltd

+86 18762990415 williamchen@cmc-chemical.com gascylindertank.com